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	Application No.	Applicant(s)
Notice of Allowability	09/500,288	NAGAHAMA ET AL.
Notice of Allowability	Examiner	Art Unit
	Wai-Sing Louie	2814
The MAILING DATE of this communication appeared All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RI of the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in this ag or other appropriate communicatio GHTS. This application is subject:	oplication. If not included
1. This communication is responsive to <u>5/27/04</u> .		
2. The allowed claim(s) is/are <u>17-24</u> .		
3. A The drawings filed on <u>08 February 2002</u> are accepted by the	ne Examiner.	
<ul> <li>4.  Acknowledgment is made of a claim for foreign priority un</li> <li>a)  All b)  Some* c)  None of the:</li> <li>1.  Certified copies of the priority documents have</li> <li>2.  Certified copies of the priority documents have</li> <li>3.  Copies of the certified copies of the priority documents have</li> <li>International Bureau (PCT Rule 17.2(a)).</li> <li>* Certified copies not received:</li> </ul>	been received. been received in Application No	***
Applicant has THREE MONTHS FROM THE "MAILING DATE" on noted below. Failure to timely comply will result in ABANDONM THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.	of this communication to file a reply ENT of this application.	complying with the requirements
<ol> <li>A SUBSTITUTE OATH OR DECLARATION must be submi INFORMAL PATENT APPLICATION (PTO-152) which give</li> </ol>	tted. Note the attached EXAMINER s reason(s) why the oath or declara	'S AMENDMENT or NOTICE OF ation is deficient.
6. CORRECTED DRAWINGS ( as "replacement sheets") must	t be submitted.	
(a) ☐ including changes required by the Notice of Draftsperso		-948) attached
1) ☐ hereto or 2) ☐ to Paper No./Mail Date		•
(b) ☐ including changes required by the attached Examiner's Paper No./Mail Date	Amendment / Comment or in the C	Office action of
Identifying indicia such as the application number (see 37 CFR 1.6 each sheet. Replacement sheet(s) should be labeled as such in the	84(c)) should be written on the drawi	ngs in the front (not the back) of
<ol> <li>DEPOSIT OF and/or INFORMATION about the depos attached Examiner's comment regarding REQUIREMENT F</li> </ol>	it of BIOLOGICAL MATERIAL i	nust be submitted. Note the
Attachment(s)  1. ☐ Notice of References Cited (PTO-892)  2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948)	5. ☐ Notice of Informal P 6. ☐ Interview Summary	ratent Application (PTO-152)
3. ☐ Information Disclosure Statements (PTO-1449 or PTO/SB/08	Paper No./Mail Dat	e
Paper No./Mail Date		
4. Examiner's Comment Regarding Requirement for Deposit		ent of Reasons for Allowance
of Biological Material	9.	
		•

Application/Control Number: 09/500,288

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## **DETAILED ACTION**

## Allowable Subject Matter

The following is an examiner's statement of reasons for allowance:

The claimed invention is a nitride semiconductor laser comprising:

- A GaN substrate having a sapphire substrate and a single-crystal GaN layer formed on the sapphire substrate, the single-crystal GaN layer formed through a lateral-growth process and defining the upper surface of the GaN substrate;
- A small-crack-preventing layer made of Al<sub>a</sub>Ga<sub>1-a</sub>N(0<a<0.1) formed directly on
  the upper surface of the GaN substrate, the small-crack-preventing layer having a
  larger AI content than the GaN layer at the interface with the GaN layer and
  having a coefficient of thermal expansion less than that of GaN thereby providing
  compression strain on the small-crack-preventing layer;</li>
- an n-type cladding layer containing AI;
- an active layer containing InGaN', and
- a p-type cladding layer containing AI.

Reference Schetzina (US 6,046,464) does not disclose a GaN substrate formed through a lateral-growth process and an AlGaN buffer layer having a larger AI content than the GaN layer at the interface.

Reference Kern et al. (US 6,194,742) do not disclose a GaN substrate formed through a lateral-growth process and an AlGaN buffer layer.

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Therefore, the above references do not disclose the claimed invention of present application and claims 17-24 are allowed.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Wai-Sing Louie whose telephone number is (571) 272-1709. The examiner can normally be reached on 7:30 AM to 4:00 PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Wael Fahmy can be reached on (571) 272-1705. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

July 6, 2004.

ONG PHAM PRIMARY EXAMINER